Fam PTO-144	9				U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY, DOCKET NO MI30-068	SERIAL NO.					
		L	JIST OF ART CITED BY APPLICANT (Use several sheets if necessary)			APPLICANT Ji Ung Lee et al.	S S					
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*EXAMINER: In copy of this form	EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 809; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.											